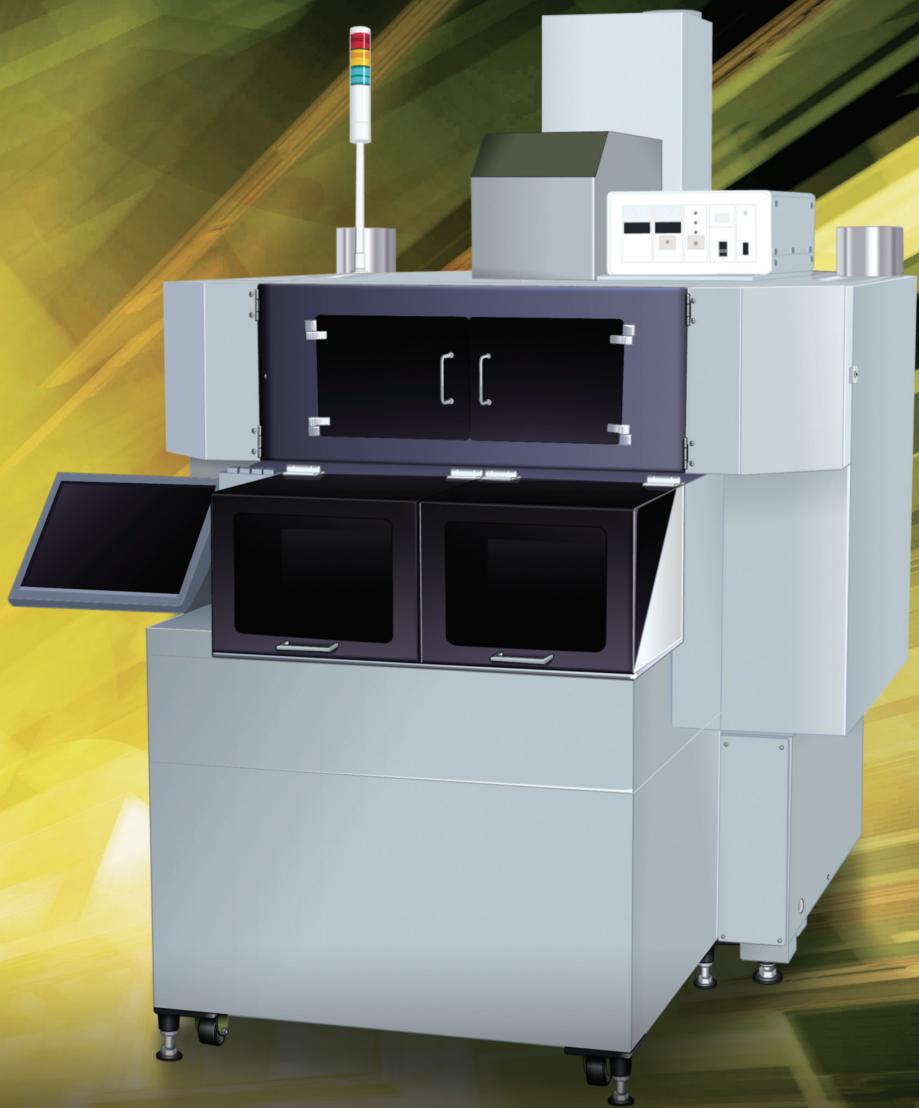




ミニステッパー／Mini Step and Repeat Exposure System

NES1W-ghi06/NES1W-i06 NES2W-ghi06/NES2W-i06



ブロードバンド対応

LED/MEMS/Power Device市場に向けた縮小投影露光装置

Newly developed i-line optics now become available on Nikon Mini Stepper NES1 and NES2 as well as current h-line optics. These new machines are our answer to highly emerging markets of LED/MEMS/Power Devices and IC back-end process.

ミニステッパー Mini Step and Repeat System

NES1W-ghi06 / NES1W-i06

NES2W-ghi06 / NES2W-i06

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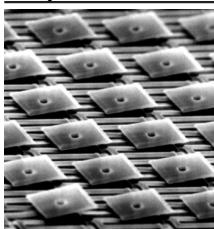
特長 Features

- ブロードバンドによる高照度化：
高照度および広露光範囲による高生産性を実現
- i線レジストへの適合：i線単波長の選択が可能
- NA拡大：解像度向上
- 安全認証対応
- 深いフォーカスマージン：
厚膜レジストや高段差に対応
- 高精度な裏面アライメント機構（オプション）
- 世界最小レベルのフットプリント
- High expose power at i-line or broadband with 22mm×22mm area is possible that contribute to improve your productivity.
- Adaptable to i-line process as well as i-line photo resist. Solely i-line exposure is also possible
- Now projection lens of which N.A is 0.13 is the best combination of larger Depth of focus and higher resolution.
- Global safety as of SEMI 2/8 and NFPA79 is now compliant on these model as standard
- Highly accurate back side alignment both Direct and IR are now available as option.
- The smallest footprint is kept as 8" wafer handling capable machine.

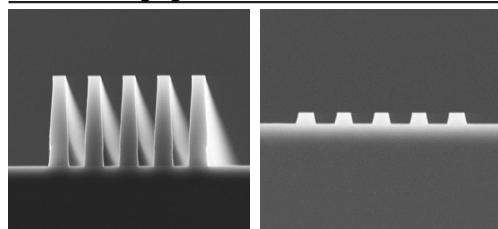
主な仕様 Specifications

| | | NES1W-ghi06 | NES1W-i06 | NES2W-ghi06 | NES2W-i06 |
|-------------------|--------------------------------------|-----------------------------------|------------------|-----------------------------------|------------------|
| 解像度 | Resolution | 2.5 μm | 2.0 μm | 2.5 μm | 2.0 μm |
| 投影レンズ縮小倍率 | Reduction Ratio | | -1/1.8 | | -1/1.8 |
| NA (開口数) | Lens-NA | | 0.13 | | 0.13 |
| 露光範囲 | Exposure Area | | 22mm□ | | 22mm□ |
| 露光波長 | Exp Light Source | 365-436nm | 365nm | 365-436nm | 365nm |
| アライメント精度 | Alignment accuracy | | 0.3μm | | 0.35μm |
| 裏面アライメント精度（オプション） | Backside alignment accuracy (Option) | | 0.8μm | | 0.8μm |
| 試料サイズ | Sample Size | Ø50mm ~ Ø150mm | | Ø150mm, Ø200mm | |
| 処理能力 | Throughput | 150mm: 100WPH | 150mm: 95WPH | 200mm: 62WPH | 200mm: 59WPH |
| 寸法/質量 | Dimensions (W×D×H) / Weight | 1,150 × 1,940 × 2,070mm / 1,750kg | | 1,440 × 2,290 × 2,100mm / 2,150kg | |

Sample MEMS Device



Excellent Imaging



安全に関するご注意 Warning

■ご使用前に「使用説明書」をよくお読みのうえ、正しくお使いください。

For your safety: Before using this product, please refer to the Technical Manual and follow the directions for proper use.



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<https://www.nikontec.co.jp/index.htm>

NIKON TEC CORPORATION
<http://www.nikon.com/products/customized/index.htm>

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